

1.The following changes to the drawings have been approved by the examiner and agreed upon by applicant---

It is noted that Figure 6F at page 3 of the drawings has been referred to as --Fig. 6E--in the specification. Applicant needs to submit a corrected drawing sheet for page 3 changing the "FIG. 6F" to --FIG. 6E--.

In order to avoid abandonment of the application, applicant must make these above agreed upon drawing changes.

2.An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

In the specification, page 1, line 14, "pending" has been changed to --U.S. Patent No. 6,663,820--

In the claims

Claim 1, line 7, "photoresist material", first occurrence, has been deleted; line 8, after "procedure", -- to form an overall patterned photoresist material comprising the first and second layers of photoresist material -- has been inserted; line 9, --overall--has

Art Unit: 1791

been inserted before “patterned”; line 9, “first and second layer of” has been deleted;
line 10, --overall—has been inserted before “patterned”

Claim 2, line 4, --overall—has been inserted before “patterned”

Claim 4, line 2, before “photoresist”, --first layer of—has been inserted; line 3,
--overall—has been inserted before “patterned”

Claim 5, line 2, “, said photoresist material comprises SU-8,” has been deleted

Claim 6, line 3, --overall—has been inserted before “patterned”

Claim 7, line 6, --overall—has been inserted before “patterned”

3. Authorization for this examiner’s amendment was given in a telephone
interview with Mr. Rose on February 24, 2010.

/Mathieu D. Vargot/

Primary Examiner, Art Unit 1791